

IN THE CLAIMS:

Please CANCEL claims 28-36 without prejudice to or disclaimer of the recited subject matter.

Please ADD new claims 37-44, as follows. Please note that all claims currently pending in this application are reproduced below for the Examiner's convenience.

1-36. (Canceled)

37. (New) An exposure apparatus for performing exposure of a substrate to light via a pattern of a reticle, said apparatus comprising:

- a reticle stage configured to hold the reticle and to move;
- a substrate stage configured to hold the substrate and to move;
- an interface configured to input information of a condition of the exposure; and
- a controller configured to determine whether the exposure is to be performed in at

least one of an acceleration period, in which said reticle stage and said substrate stage are accelerated, and a deceleration period, in which said reticle stage and said substrate stage are decelerated, based on the input information.

38. (New) An apparatus according to claim 37, wherein the condition of the exposure includes at least one of a shot size, a shot layout of the exposure to be performed, an alignment measure, a shot layout of the exposure having been performed, a shot position, and an accuracy required with respect to moving said reticle stage and said substrate stage.

39. (New) An apparatus according to claim 38, wherein the condition of the exposure includes a synchronization accuracy with respect to moving said reticle stage and said substrate stage.

40. (New) A method of manufacturing a device, said method comprising steps of:  
performing exposure of a substrate to light via a pattern of a reticle using an exposure apparatus as defined in claim 37;  
developing the exposed substrate; and  
processing the developed substrate to manufacture the device.

41. (New) An apparatus according to claim 37, wherein said controller is configured to perform the determination based on a user's indication if a manual specification mode is specified as a determination mode of said controller.

42. (New) An exposure apparatus for performing exposure of a substrate to light via a pattern of a reticle, said apparatus comprising:  
an interface configured to input information of a condition of the exposure; and  
a controller configured to select an exposure method to be used among a plurality of exposure methods so that a measure, required for exposure of a substrate, obtained with respect to a previous exposure of a substrate, is diverted, based on the input information.

43. (New) An apparatus according to claim 42, wherein the plurality of exposure methods includes at least one of a static exposure with the substrate standing still while the exposure is performed, a constant speed exposure with the substrate moving at a constant speed while the exposure is performed and a changing speed exposure with the substrate moving at a changing speed while the exposure is performed.

44. (New) A method of manufacturing a device, said method comprising steps of:  
performing exposure of a substrate to light via a pattern of a reticle using an exposure apparatus as defined in claim 42;  
developing the exposed substrate; and  
processing the developed substrate to manufacture the device.